IN THE CLAIMS:

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1 - 14 (Cancelled)

- 15. (Currently Amended) A continuous process for the preparation of silane of formula SiH₄ by catalytic disproportionation of trichlorosilane of formula SiHCl₃ to form SiH₄ and silicon tetrachloride of formula SiCl₄ in a reactive/distillative reaction zone comprising
- (a) introducing SiHCl₃ into a reactive/distillative reaction zone comprising a catalyst bed of a catalytically active solid at a pressure of 1 to 50 bar to form a lower-boiling SiH₄
 -containing product and a higher-boiling SiCl₄-containing bottom product; and
- (b) removing the lower-boiling SiH₄-containing product from the reactive/distillative reaction zone and condensing the SiH₄-containing product in an intermediate condensation at a temperature in the range from -25°C -5°C to 50°C 40°C;
- intermediate condensation into a rectifying section and increasing the SiH₄concentration in the SiH₄-containing product which is not condensed in the intermediate
 condensation;
- (d) further condensing any SiH₄-containing product that is not condensed in the intermediate condensation and concentrated in the rectifying section in an overhead condenser from which the SiH₄-containing product is discharged as final product.
 - 16. (Previously Presented) A process according to Claim 15 wherein the pressure in the

catalyst bed is from 1 to 10 bar.

17. (Cancelled)

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- 18. (Currently Amended) A process according to Claim 17 15 wherein the product mixture obtained SiH₄-containing product discharged is separated in the overhead condenser is separated at a pressure higher than the pressure employed in the intermediate condensation.
- 19. (Currently Amended) A process according to Claim 17 15 wherein all or part of the chlorosilane is returned to the reactive/distillative reaction zone.
- 20. (Currently Amended) An installation for the continuous preparation of silane of formula SiH₄ by catalytic disproportionation of trichlorosilane of formula SiHCl₃ to form SiH₄ and silicon tetrachloride of formula SiCl₄ in a reaction column having
- (1) a reactive/distillative reaction zone comprising a catalyst bed made of solid bodies of catalytically active solid and through which the disproportionation products and trichlorsilane can flow,
- (2) an inlet for introducing SiHCl, into the reactive zone,
- (3) an overhead condenser connected to the reaction column for condensing the SiH₄containing product that is formed and having an outlet for condensed SiH₄ at the
 overhead condenser,

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- (4) at least one intermediate condenser arranged between the reactive/distillative reaction zone and the overhead condenser, wherein the <u>at least one</u> intermediate condenser is operated at a temperature in the range from -25°C -5°C to 50°C 40°C.
- (5) a rectifying section for increasing the SiH₄-concentration in the lower-boiling SiH₄-containing product which is not condensed in the at least one intermediate condenser being arranged downstream of the at least one intermediate condenser in a direction of flow of the lower-boiling SiH₄-containing product coming from the at least one intermediate condenser, and (6) an outflow for SiCl₄ obtained as bottom product, for carrying out the process according to Claim † 15.
 - 21. (Cancelled)
- 22. (Currently Amended) An installation according to Claim 20 wherein the <u>at least one</u> intermediate condenser is arranged above the catalyst bed.
 - 23. (Cancelled)
- 24. (Currently Amended) An installation according to Claim 20 wherein a separation column for separating SiH₄-containing product fractions from higher-boiling chlorosilane components is arranged downstream of the <u>at least one</u> intermediate condenser in the <u>at least one</u> intermediate direction of flow of the lower-boiling product mixture coming from the <u>at least one</u> intermediate

condenser.

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- 25. (Previously Presented) An installation according to Claim 24 wherein the separation column is arranged downstream of the rectifying section.
- 26. (Currently Amended) An installation according to Claim 25 wherein a the overhead condenser is arranged between the rectifying section and the separation column.
- 27. (Currently Amended) An installation according to Claim 24 wherein the separation column is operated at a pressure higher than the pressure in the <u>at least one</u> intermediate condenser and the product that is conducted to the separation column is compressed.
- 28. (Currently Amended) An installation according to Claim 24 wherein a branch line that opens into a reactive/distillative reaction zone of the reaction column is connected to the a bottom outlet of the separation column.
- 29. (New) A process for producing silane, the process comprising the steps of: providing a reactive/distillative reaction zone including a catalyst bed of a catalytically active solid forming a lower-boiling SiH₄ -containing product and a higher-boiling SiCl₄-containing bottom product;
 - introducing SiHCl, into the reactive/distillative reaction zone at a pressure of 1 to 50

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bar and forming the lower-boiling SiH₄ -containing product and the higher-boiling SiCl4-containing bottom product;

removing the lower-boiling SiH₄-containing product from the reactive/distillative reaction zone;

cooling the SiH₄-containing product after said removing in an intermediate condensation with temperatures in the range from -5°C to 40°C;

providing a rectifying section;

introducing the lower-boiling SiH₄-containing product which is not condensed during said cooling into a rectifying section to increasing a SiH₄-concentration in the SiH₄-containing product;

condensing the SiH₄-containing product from the rectifying section in an overhead condenser from which the SiH₄-containing product is discharged as final product.